

AMENDMENT TRANSMITTAL LETTER					Docket No. M4065.0210/P210		
Application No. 09/588,008		Filing Date June 6, 2000		Examiner Vikki H. Trinh		Art Unit 2814	
Applicant(s): Yar	ng, et al.						
Invention: IMPRO	OVED MEMOR	Y CELL CAPA	CITOR STRU	JCTURE AND MET	HOD OF	FORMATION	
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	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate			
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Independent Claims	3	- 3 =	0	x			
Multiple Dependent Claims (check if applicable)							
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Thomas J. D'A	mico	<u> </u>		Dated.	Mai Cii Zi	3, <u>2000</u>	
Attorney Reg. I DICKSTEIN SH 2101 L Street I Washington, D (202) 828-2232	No.: 28,371 HAPIRO MORII NW C 20037-1526		Y LLP		March 26	MAR 27 2003 OLOGY CENTER 28,00	VEOCH ED
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Docket No.: M4065.0210/P2 (PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: Yang et al.

Application No.: 09/588,008

Group Art Unit: 2814

Examiner: Vikki H. Trinh Filed: June 6, 2000

For: IMPROVED MEMORY CELL CAPACITOR

STRUCTURE AND METHOD OF

**FORMATION** 

## AMENDMENT

Commissioner for Patents Washington, DC 20231

Dear Sir:

This paper is in response to the Office Action dated December 26, 2002. Please amend the above-captioned U.S. Patent application as follows:

## In the Claims:

Please rewrite claims 1, 26-28 and 98 as follows:

1. (twice amended) A capacitor for a semiconductor device, said capacitor comprising:

a bottom conducting layer;

a dielectric layer formed over said bottom conducting layer; and

an annealed top conducting layer formed over said dielectric layer, said top conducting layer comprising an oxygen permeable material.